ABSTRACT OF THE DISCLOSURE

A black matrix and a color filter are formed on a substrate, a indium-tin-oxide (ITO) common electrode are deposited thereon and then protrusion pattern made of sensitive material such as photoresist are formed on the common electrode with 3 to 20 micron width. A vertical alignment layer is coated thereon to complete a color filter substrate. After a thin film transistor (TFT) and a passivation film are formed on the other substrate, ITO is deposited on the passivation film and patterned to form a pixel electrode which contains open areas with 3 to 20 micron width. Then, a vertical alignment layer is coated to complete a TFT substrate. Two substrates are assembled in the manner that the apertures and the protrusion patterns are arranged on shifts and liquid crystal having negative dielectric anisotropy is injected between the substrates. Each Polarizer is attached at the outer surfaces of the LCD substrates. Compensation films may be attached between the polarizer and the substrate.